Photomask Japan 2018 Oral Presentation

**April 18**

**10:10 - 10:40**

**Keynote Lecture**

- **Evoluational Memory Technology**
  - Name: Naohiro Aoto
  - Affiliation: Micron Memory Japan

**April 19**

**9:00 - 10:30**

**EUV masks (I)**

- **Invited**
  - Presentation Title: EUV Initiative Survey Report Greater Confidence in EUV and Mask Process Correction Requirements
  - Name: Akira Fujimura
  - Affiliation: Icave LLC

**10:50 - 11:50**

**EUV source for inspection**

- **Invited**
  - Presentation Title: Impact of Dispersed Properties and Non-YAG Laser Characteristics on the Angular Distribution of EUV Radiation of a LPP EUV Light Source for HVM EUV Mask and Blank Inspection
  - Name: Marco Marz Weber
  - Affiliation: ETH Zurich, Laboratory for Energy Conversion

**13:20 - 14:40**

**25th anniversary special session**

- **Invited**
  - Presentation Title: ``Mask Technology'', the Key of Moore's Law Scaling
  - Name: Shigehiro Oikawa
  - Affiliation: ALTECS Corporation

**April 20**

**10:10 - 10:40**

**EUV Masks (I)**

- **Invited**
  - Presentation Title: Progress on Actinic Blank Inspection and Optimization of EUV Mask Observation
  - Name: Yoshihiro Miyazaki
  - Affiliation: Nikon

**11:00 - 12:10**

**EUV masks (II)**

- **Invited**
  - Presentation Title: Development of Transparent Backside Film for EUV Blank
  - Name: Yusuke Ishikawa
  - Affiliation: HOYA Corporation

**12:40 - 15:20**

**EUV masks (IV)**

- **Invited**
  - Presentation Title: Development of Closed-Optical EUV Pellicle
  - Name: Yosuke Ono
  - Affiliation: Mitsubishi Chemicals Inc.